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PATENT



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

INVENTOR: C. Obszarny

EXAMINER: P. Kim

SERIAL NO.: 09/116,395 ✓

ART UNIT: 2851

FILING DATE: 16 July 1998 ✓

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#1213  
gmm  
6-2400

FOR: **APPARATUS AND METHOD FOR IN-SITU ADJUSTMENT OF  
LIGHT TRANSMISSION IN A PHOTOLITHOGRAPHY  
PROCESS**

**AMENDMENT**

Assistant Commissioner of Patents  
Washington, DC 20231

**RECEIVED**  
JUN 23 2000  
TECHNOLOGY CENTER 2800

Dear Sir:

Responsive to the Office Action mailed 20 March 2000, please amend the application  
as follows:

**In the Claims**

Please amend claims 1, 3, 7, 17 and 18 as follows:

1. (twice amended) An apparatus for varying optical transmission intensity on a substrate  
wafer in a photolithography process comprising:
- a first polarizer capable of adjustment during optical transmission such that an optical  
image focused on said substrate wafer is varied in contrast, said adjustment made  
relative to a second polarizer; and,
- a photo mask patterned with a plurality of optically transparent and optically opaque  
regions, wherein said transparent regions are impregnated with said second  
polarizer[,] fixed in a predetermined direction, and said opaque regions comprise a

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21